

EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|--------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------|------------------------------|------------------|---------|------------------|
| L1 | 1 | ("6897149").PN. | US-PGPUB; USPAT; USOCR | OR | OFF | 2007/11/06 14:09 |
| L4 | 227 | (gas near2 (supply or inlet)) near3 ground\$3 | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/06 15:14 |
| L5 | 16 | (clean\$4 or etch\$4 or remov\$4) and (substrate or semiconductor or wafer) and ((deposit or residue or contaminant or contamination or film) near3 (fluorine near2 added near2 carbon)) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/06 15:02 |
| L6 | 8 | (clean\$4) and (substrate or semiconductor or wafer) and ((deposit or residue or contaminant or contamination or film) near3 (fluorine near2 added near2 carbon)) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/06 15:02 |
| L7 | 91 | 4 and plasma | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/06 15:14 |
| S1 | 766 | (134/1.1).CCLS. | US-PGPUB; USPAT; USOCR | OR | OFF | 2007/11/05 11:15 |
| S2 | 1725 | (438/710).CCLS. | US-PGPUB; USPAT; USOCR | OR | OFF | 2007/11/05 11:17 |
| S3 | 18 | S1 and (tank or container or chamber) and (stage or susceptor or hold\$3) and (RF or radio) and exhaust\$4 and (shower\$1head or (shower adj (head or plate)) or manifold or sprayer or ((distribution or diffuser) adj plate) or (gas adj injection adj orifices)) and antenna and ((oxygen or "O.sub.2" or O2 or Ox or On or Osubx or Osubn or "O.subx" or "O.subn" or "O.sub.x" or "O.sub.n") or (Hydrogen or Hydrogen\$3 or H2 or Hx or Hn or Hsubx or Hsubn or "H.subx" or "H. subn" or "H.sub.x" or "H.sub.n") or (water or aqueous or H2O or (H2O or HxO or HnO or "H.sub2O" or "H. subxO" or "H.subnO" or "H.sub.2O" or "H.sub.x.O" or "H.sub.n.O")) or (C4F8 or "C.sub.4F.sub.8" or "C.sub.xF.sub. x" or "C.sub.nF.sub.n" or "C.sub.xF. sub.n" or "C.sub.nF.sub.x" or Octafluorocyclobutane or (RC adj "318"))) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 11:23 |

EAST Search History

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| S4 | 626 | (tank or container or chamber) and (stage or susceptor or hold\$3) and (RF or radio) and exhaust\$4 and (shower\$1head or (shower adj (head or plate)) or manifold or sprayer or ((distribution or diffuser) adj plate) or (gas adj injection adj orifices)) and antenna and ((oxygen or "O.sub.2" or O2 or Ox or On or Osubx or Osubn or "O.subx" or "O.subn" or "O.sub.x" or "O.sub.n") or (Hydrogen or Hydrogen\$3 or H2 or Hx or Hn or Hsubx or Hsubn or "H. subx" or "H.subn" or "H.sub.x" or "H. sub.n") or (water or aqueous or H2O or (H2O or HxO or HnO or "H.sub2O" or "H. subxO" or "H.subnO" or "H.sub.2.O" or "H.sub.x.O" or "H.sub.n.O")) or (C4F8 or "C.sub.4F.sub.8" or "C.sub.xF.sub. x" or "C.sub.nF.sub.n" or "C.sub.xF. sub.n" or "C.sub.nF.sub.x" or Octafluorocyclobutane or (RC adj "318"))) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 11:21 |
| S5 | 37 | "134"/\$.ccls. and (tank or container or chamber) and (stage or susceptor or hold\$3) and (RF or radio) and exhaust\$4 and (shower\$1head or (shower adj (head or plate)) or manifold or sprayer or ((distribution or diffuser) adj plate) or (gas adj injection adj orifices)) and antenna and ((oxygen or "O.sub.2" or O2 or Ox or On or Osubx or Osubn or "O.subx" or "O.subn" or "O.sub.x" or "O.sub.n") or (Hydrogen or Hydrogen\$3 or H2 or Hx or Hn or Hsubx or Hsubn or "H. subx" or "H.subn" or "H.sub.x" or "H. sub.n") or (water or aqueous or H2O or (H2O or HxO or HnO or "H.sub2O" or "H. subxO" or "H.subnO" or "H.sub.2.O" or "H.sub.x.O" or "H.sub.n.O")) or (C4F8 or "C.sub.4F.sub.8" or "C. sub.xF.sub.x" or "C.sub.nF.sub.n" or "C.sub.xF.sub.n" or "C.sub.nF.sub.x" or Octafluorocyclobutane or (RC adj "318"))) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 13:22 |

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| S6 | 18 | S1 and ((clean\$4 or rins\$4 or treat\$4 or etch\$4) same (tank or container or chamber)) and (substrate or semiconductor or wafer) and (stage or susceptor or hold\$3) and (RF or radio) and exhaust\$4 and (shower\$1head or (shower adj (head or plate)) or manifold or sprayer or ((distribution or diffuser) adj plate) or (gas adj injection adj orifices)) and antenna and ((oxygen or "O.sub.2" or O2 or Ox or On or Osubx or Osubn or "O.subx" or "O.subn" or "O.sub.x" or "O.sub.n") or (Hydrogen or Hydrogen\$3 or H2 or Hx or Hn or Hsubx or Hsubn or "H. subx" or "H.subn" or "H.sub.x" or "H. sub.n") or (water or aqueous or H2O or (H2O or HxO or HnO or "H.sub2O" or "H.subxO" or "H.subnO" or "H.sub.2.O" or "H.sub.x.O" or "H.sub.n.O")) or (C4F8 or "C.sub.4F.sub.8" or "C. sub.xF.sub.x" or "C.sub.nF.sub.n" or "C.sub.xF.sub.n" or "C.sub.nF.sub.x" or Octafluorocyclobutane or (RC adj "318"))) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 11:38 |
| S7 | 412 | ((clean\$4 or rins\$4 or treat\$4 or etch\$4) same (tank or container or chamber)) and (substrate or semiconductor or wafer) and (stage or susceptor or hold\$3) and (RF or radio) and exhaust\$4 and (shower\$1head or (shower adj (head or plate)) or manifold or sprayer or ((distribution or diffuser) adj plate) or (gas adj injection adj orifices)) and antenna and ((oxygen or "O.sub.2" or O2 or Ox or On or Osubx or Osubn or "O.subx" or "O.subn" or "O.sub.x" or "O.sub.n") or (Hydrogen or Hydrogen\$3 or H2 or Hx or Hn or Hsubx or Hsubn or "H. subx" or "H.subn" or "H.sub.x" or "H. sub.n") or (water or aqueous or H2O or (H2O or HxO or HnO or "H.sub2O" or "H.subxO" or "H.subnO" or "H.sub.2.O" or "H.sub.x.O" or "H.sub.n.O")) or (C4F8 or "C.sub.4F.sub.8" or "C. sub.xF.sub.x" or "C.sub.nF.sub.n" or "C.sub.xF.sub.n" or "C.sub.nF.sub.x" or Octafluorocyclobutane or (RC adj "318"))) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/06 14:09 |

EAST Search History

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| S8 | 36 | "134"/\$.ccls. and ((clean\$4 or rins\$4 or treat\$4 or etch\$4) same (tank or container or chamber)) and (substrate or semiconductor or wafer) and (stage or susceptor or hold\$3) and (RF or radio) and exhaust\$4 and (shower\$1head or (shower adj (head or plate)) or manifold or sprayer or ((distribution or diffuser) adj plate) or (gas adj injection adj orifices)) and antenna and ((oxygen or "O.sub.2" or O2 or Ox or On or Osubx or Osubn or "O.subx" or "O.subn" or "O.sub.x" or "O.sub.n") or (Hydrogen or Hydrogen\$3 or H2 or Hx or Hn or Hsubx or Hsubn or "H.subx" or "H.subn" or "H.sub.x" or "H.sub.n") or (water or aqueous or H2O or (H2O or HxO or HnO or "H.sub2O" or "H. subxO" or "H.subnO" or "H.sub.2O" or "H.sub.x.O" or "H.sub.n.O")) or (C4F8 or "C.sub.4F.sub.8" or "C.sub.xF.sub.x" or "C.sub.nF.sub.n" or "C.sub.xF. sub.n" or "C.sub.nF.sub.x" or Octafluorocyclobutane or (RC adj "318"))) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 13:44 |
| S9 | 427 | ((clean\$4 or rins\$4 or treat\$4 or etch\$4) same (tank or container or chamber)) and (substrate or semiconductor or wafer) and (stage or susceptor or hold\$3) and (RF or radio) and exhaust\$4 and (shower\$1head or (shower adj (head or plate)) or manifold or sprayer or ((distribution or diffuser) adj plate) or (gas adj injection adj orifices)) and antenna and ((oxygen or "O.sub.2" or O2 or Ox or On or Osubx or Osubn or "O.subx" or "O.subn" or "O.sub.x" or "O.sub.n") or (Hydrogen or Hydrogen\$3 or H2 or Hx or Hn or Hsubx or Hsubn or "H. subx" or "H.subn" or "H.sub.x" or "H. sub.n") or (water or aqueous or H2O or (H2O or HxO or HnO or "H.sub2O" or "H.subxO" or "H.subnO" or "H.sub.2O" or "H.sub.x.O" or "H.sub.n.O")) or fluorine or (C4F8 or "C.sub.4F.sub.8" or "C.sub.xF.sub.x" or "C.sub.nF. sub.n" or "C.sub.xF.sub.n" or "C.sub. nF.sub.x" or Octafluorocyclobutane or (RC adj "318"))) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 11:44 |

EAST Search History

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| S10 | 19 | S1 and ((clean\$4 or rins\$4 or treat\$4 or etch\$4) same (tank or container or chamber)) and (substrate or semiconductor or wafer) and (stage or susceptor or hold\$3) and (RF or radio) and exhaust\$4 and (shower\$1head or (shower adj (head or plate)) or manifold or sprayer or ((distribution or diffuser) adj plate) or (gas adj injection adj orifices)) and antenna and ((oxygen or "O.sub.2" or O2 or Ox or On or Osubx or Osubn or "O.subx" or "O.subn" or "O.sub.x" or "O.sub.n") or (Hydrogen or Hydrogen\$3 or H2 or Hx or Hn or Hsubx or Hsubn or "H. subx" or "H.subn" or "H.sub.x" or "H. sub.n") or (water or aqueous or H2O or (H2O or HxO or HnO or "H.sub2O" or "H.subxO" or "H.subnO" or "H.sub.2.O" or "H.sub.x.O" or "H.sub.n.O")) or fluorine or (C4F8 or "C.sub.4F.sub.8" or "C.sub.xF.sub.x" or "C.sub.nF. sub.n" or "C.sub.xF.sub.n" or "C.sub. nF.sub.x" or Octafluorocyclobutane or (RC adj "318"))) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 11:54 |
| S11 | 37 | "134"/\$.ccls. and ((clean\$4 or rins\$4 or treat\$4 or etch\$4) same (tank or container or chamber)) and (substrate or semiconductor or wafer) and (stage or susceptor or hold\$3) and (RF or radio) and exhaust\$4 and (shower\$1head or (shower adj (head or plate)) or manifold or sprayer or ((distribution or diffuser) adj plate) or (gas adj injection adj orifices)) and antenna and ((oxygen or "O.sub.2" or O2 or Ox or On or Osubx or Osubn or "O.subx" or "O.subn" or "O.sub.x" or "O.sub.n") or (Hydrogen or Hydrogen\$3 or H2 or Hx or Hn or Hsubx or Hsubn or "H.subx" or "H. subn" or "H.sub.x" or "H.sub.n") or (water or aqueous or H2O or (H2O or HxO or HnO or "H.sub2O" or "H. subxO" or "H.subnO" or "H.sub.2.O" or "H.sub.x.O" or "H.sub.n.O")) or fluorine or (C4F8 or "C.sub.4F.sub.8" or "C.sub.xF.sub.x" or "C.sub.nF. sub.n" or "C.sub.xF.sub.n" or "C.sub. nF.sub.x" or Octafluorocyclobutane or (RC adj "318"))) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 11:45 |

EAST Search History

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| S12 | 5 | S1 and ((clean\$4 or rins\$4 or treat\$4 or etch\$4) same (tank or container or chamber)) and (substrate or semiconductor or wafer) and (stage or susceptor or hold\$3) and (RF or radio) and exhaust\$4 and (shower\$1head or (shower adj (head or plate)) or manifold or sprayer or ((distribution or diffuser) adj plate) or (gas adj injection adj orifices)) and antenna and ((oxygen or "O.sub.2" or O2 or Ox or On or Osubx or Osubn or "O.subx" or "O.subn" or "O.sub.x" or "O.sub.n") and (Hydrogen or Hydrogen\$3 or H2 or Hx or Hn or Hsubx or Hsubn or "H.subx" or "H.subn" or "H.sub.x" or "H.sub.n") and (water or aqueous or H2O or (H2O or HxO or HnO or "H.sub2O" or "H.subxO" or "H.subnO" or "H.sub.2.O" or "H.sub.x.O" or "H.sub.n.O")) and (fluorine or (C4F8 or "C.sub.4F.sub.8" or "C.sub.xF.sub.x" or "C.sub.nF.sub.n" or "C.sub.xF.sub.n" or "C.sub.nF.sub.x" or Octafluorocyclobutane or (RC adj "318")))) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 11:57 |
| S13 | 11 | "134"/\$.ccls. and ((clean\$4 or rins\$4 or treat\$4 or etch\$4) same (tank or container or chamber)) and (substrate or semiconductor or wafer) and (stage or susceptor or hold\$3) and (RF or radio) and exhaust\$4 and (shower\$1head or (shower adj (head or plate)) or manifold or sprayer or ((distribution or diffuser) adj plate) or (gas adj injection adj orifices)) and antenna and ((oxygen or "O.sub.2" or O2 or Ox or On or Osubx or Osubn or "O.subx" or "O.subn" or "O.sub.x" or "O.sub.n") and (Hydrogen or Hydrogen\$3 or H2 or Hx or Hn or Hsubx or Hsubn or "H.subx" or "H.subn" or "H.sub.x" or "H.sub.n") and (water or aqueous or H2O or (H2O or HxO or HnO or "H.sub2O" or "H.subxO" or "H.subnO" or "H.sub.2.O" or "H.sub.x.O" or "H.sub.n.O")) and (fluorine or (C4F8 or "C.sub.4F.sub.8" or "C.sub.xF.sub.x" or "C.sub.nF.sub.n" or "C.sub.xF.sub.n" or "C.sub.nF.sub.x" or Octafluorocyclobutane or (RC adj "318")))) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 12:09 |

EAST Search History

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| S15 | 0 | "134"/\$.ccls. and ((clean\$4 or rins\$4 or treat\$4 or etch\$4) same (tank or container or chamber)) and (substrate or semiconductor or wafer) and (stage or susceptor or hold\$3) and (RF or radio) and exhaust\$4 and (shower\$1head or (shower adj (head or plate)) or manifold or sprayer or ((distribution or diffuser) adj plate) or (gas adj injection adj orifices)) and antenna and ((oxygen or "O.sub.2" or O2 or Ox or On or Osubx or Osubn or "O.subx" or "O.subn" or "O.sub.x" or "O.sub.n") and (Hydrogen or Hydrogen\$3 or H2 or Hx or Hn or Hsubx or Hsubn or "H.subx" or "H. subn" or "H.sub.x" or "H.sub.n") and (water or aqueous or H2O or (H2O or HxO or HnO or "H.sub2O" or "H. subxO" or "H.subnO" or "H.sub.2.O" or "H.sub.x.O" or "H.sub.n.O")) and (C4F8 or "C.sub.4F.sub.8" or "C.sub. xF.sub.x" or "C.sub.nF.sub.n" or "C. sub.xF.sub.n" or "C.sub.nF.sub.x" or Octafluorocyclobutane or (RC adj "318"))) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 16:11 |
| S16 | 23 | "134"/\$.ccls. and ((clean\$4 or rins\$4 or treat\$4 or etch\$4) same (tank or container or chamber)) and (substrate or semiconductor or wafer) and (stage or susceptor or hold\$3) and (RF or radio) and exhaust\$4 and (shower\$1head or (shower adj (head or plate)) or manifold or sprayer or ((distribution or diffuser) adj plate) or (gas adj injection adj orifices)) and antenna and (water or aqueous or H2O or (H2O or HxO or HnO or "H. sub2O" or "H.subxO" or "H.subnO" or "H.sub.2.O" or "H.sub.x.O" or "H.sub. n.O")) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 13:48 |

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| S17 | 23 | "134"/\$.ccls. and ((clean\$4 or rins\$4 or treat\$4) same (tank or container or chamber)) and (substrate or semiconductor or wafer) and (stage or susceptor or hold\$3) and (RF or radio) and exhaust\$4 and (shower\$1head or (shower adj (head or plate)) or manifold or sprayer or ((distribution or diffuser) adj plate) or (gas adj injection adj orifices)) and antenna and (water or aqueous or H2O or (H2O or HxO or HnO or "H.sub2O" or "H.subxO" or "H.subnO" or "H.sub.2.O" or "H.sub.x.O" or "H.sub.n.O")) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 13:50 |
| S18 | 18 | "134"/\$.ccls. and ((clean\$4 or rins\$4 or treat\$4) near5 (tank or container or chamber)) and (substrate or semiconductor or wafer) and (stage or susceptor or hold\$3) and (RF or radio) and exhaust\$4 and (shower\$1head or (shower adj (head or plate)) or manifold or sprayer or ((distribution or diffuser) adj plate) or (gas adj injection adj orifices)) and antenna and (water or aqueous or H2O or (H2O or HxO or HnO or "H.sub2O" or "H.subxO" or "H.subnO" or "H.sub.2.O" or "H.sub.x.O" or "H.sub.n.O")) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 14:03 |
| S19 | 3102 | "134"/\$.ccls. and ((clean\$4 or rins\$4 or treat\$4) near5 (tank or container or chamber)) and (substrate or semiconductor or wafer) and (water or aqueous or H2O or (H2O or HxO or HnO or "H.sub2O" or "H.subxO" or "H.subnO" or "H.sub.2.O" or "H.sub.x.O" or "H.sub.n.O")) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 14:04 |
| S20 | 239 | "134"/1.1.ccls. and ((clean\$4 or rins\$4 or treat\$4) near5 (tank or container or chamber)) and (substrate or semiconductor or wafer) and (water or aqueous or H2O or (H2O or HxO or HnO or "H.sub2O" or "H.subxO" or "H.subnO" or "H.sub.2.O" or "H.sub.x.O" or "H.sub.n.O")) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 14:05 |
| S21 | 311 | (clean\$4 or rins\$4 or treat\$4 or etch\$4) and (substrate or semiconductor or wafer) and ((supply near4 (plasma or process)) same (conduct\$4 and ground\$4)) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 14:07 |

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| S22 | 8 | 134/1.1.ccls. and (clean\$4 or rins\$4 or treat\$4 or etch\$4) and (substrate or semiconductor or wafer) and ((supply near4 (plasma or process)) same (conduct\$4 and ground\$4)) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 14:17 |
| S23 | 1 | 134/1.1.ccls. and (clean\$4 or rins\$4 or treat\$4 or etch\$4) and (substrate or semiconductor or wafer) and ((supply near4 (plasma or process)) same (conduct\$4 near20 ground\$4)) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 14:19 |
| S24 | 1 | 134/1.1.ccls. and (clean\$4 or rins\$4 or treat\$4 or etch\$4) and (substrate or semiconductor or wafer) and (((supply near4 (plasma or process)) same (conduct\$4 near20 ground\$4))) | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 14:27 |
| S25 | 21 | antenna same wave\$1guide same body same ((many or multiple or plural\$4) near2 (holes or openings or slots or slits)) same dielectric | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 14:55 |
| S26 | 4 | ("20040011379" "20040065344" "478 6352" "6925731").PN. | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 16:02 |
| S27 | 643 | ohmi near2 tadahiro.in. | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 16:02 |
| S28 | 97 | masaki near2 hirayama.in. | US-PGPUB; USPAT; USOCR | OR | ON | 2007/11/05 16:02 |
| S29 | 558 | ohmi near2 tadahiro.in. | EPO; JPO; DERWENT | OR | ON | 2007/11/05 16:02 |
| S30 | 158 | masaki near2 hirayama.in. | EPO; JPO; DERWENT | OR | ON | 2007/11/05 16:02 |
| S31 | 4334 | (134/42,902).CCLS. | US-PGPUB; USPAT; USOCR | OR | OFF | 2007/11/05 16:11 |